Receipt date: 04/06/2006

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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No.

TBD

Applicant

Yuichiro Sasaki et al.

Filed

Herewith

Title

"METHOD FOR MAKING JUNCTION AND

PROCESSED MATERIAL FORMED USING THE SAME"

Confirmation No.

TC/A.U.

TBD TBD

Examiner

TBD

International App. No.:

PCT/JP2004/015308

International Flg. Date:

October 8, 2004

Customer No.

52054

Docket No.

40201

INFORMATION DISCLOSURE STATEMENT

Mail Stop PCT Commissioner for Patents P.O. Box 1450 Alexandria, Va. 22313-1450

Sir/Madam:

In accordance with Rule 56, applicants are aware of the publications listed in the International Search Report (ISR, copy enclosed) and in the enclosed copy of Patent Office Form 1449. Copies of the publications cited in the International Search Report are not enclosed as they were previously forwarded by the International Bureau, however, a copy of each publication cited in the specification is enclosed.

If there are any fees required by this communication, please charge such fees to our Deposit Account No. 16-0820, Order No. 40201.

Respectfully submitted,

PEARNE & GORDON LLP

1801 East 9th Street **Suite 1200** Cleveland, Ohio 44114-3108 (216) 579-1700

AND THE BEEN OF SECOND SOURCE BED EXCEPT WHERE LINED THROUGH. /GF/

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APPLICANT: INFORMATION DISCLOSURE CITATION BY APPLICANT BY APPLICANT APPLICANT: Yuichiro Sasaki et al.									al.			
(USE SEVERAL SHEETS IF NECESSARY)						FILING DATE: Herewith				GROUP ART UNIT: TBD		
U.S. PATENT DOCUMENTS												
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	Н	5-206053	08/1993								d on ISR	
	I	9-17867	01/1997			-/					d on ISR	
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CTHER REFERENCES (L. L. L												
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)												
	L	Talwar et al., "Study of Laser Thermal Processing (LPT) to Meet Sub 130 nm Node Shallow Junction Requirements", 2000, pages 175-177 (Cited in Specification)										
	М	Ito et al., "Flash Lamp Annealing Technology for Ultra-shallow Junction Formation", Extended Abstract of International Workshop on Junction Technoloy, 2002, pages 23-26 (Cited in Specification)										
	N	Yamamoto et al., "Impact of Pre-Amorphization for the Reduction of Contact Resistance Using Laser Thermal Process", Extended Abstract of International Workshop on Junction Technoloy, 2002, pages 27-30 (Cited in Specification)										
	0	Kagawa et al., "Influence of Pulse Duration on KrF Excimer Laser Annealing Process for Ultra Shallow Junction Formation, Extended Abstract of International Workshop on Junction Technoloy, 2002, pages 31-34 (Cited in Specification)										
	P	Ito et al., "Improvement of Threshold Voltage Roll-off by Ultra-shallow Junction Formed by Flash Lamp Annealing", 2003, pages 53-54 (Cited in Specification)										
Examiner	:	/George Fourson/			Date	Date Considered			05/2	05/20/2011		
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